ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18 Stylesheet Version v18.0

> Title of Invention

SYSTEMS FOR INSPECTING WAFERS AND RETICLES WITH INCREASED RESOLUTION

Application Number:

10/725744

Confirmation Number:

3066

First Named Applicant:

Steven Lange Attorney Docket Number: 5589-05201

Search string:

(5825043 or 6191429 or 5298939 or 4346164

or 6493156 or 5610683 or 5040020 or 4898804 or 4544626 or 4509852 or 5023424 or 5900354

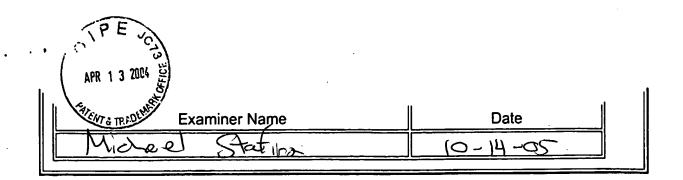
or 5004307 or 5121256).pn.

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
M	1	5825043	1998-10-20	Suwa			•
	2	6191429	2001-02-20	Suwa			
M	3	5298939	1994-03-29	Swanson et al.			
	4	4346164	1982-08-24	. Tabarelli et al.			
	5	6493156	2002-12-10	Oh et al.			
	6	5610683	1997-03-11	Takahashi		•	
	7	5040020	1991-08-13	Rauschenbach et al.			
	8	4898804	1990-02-06	Rauschenbach et al.			
	9	4544626	1985-10-01	Sullivan			
D	10	4509852	1985-04-09	Tabarelli et al.			
	11	5023424	1991-06-11	Vaught			
129	12	5900354	1999-05-04	Batchelder			
	13	5004307	1991-04-02	Kino et al.			
	14	5121256	1992-06-09	Corle et al.]		

Signature



Page 1 of 1

PTO-1449 (modified) ATTY, DKT, NO. 5589-05201 SERIAL NO. 10/725,744 Patents and Publications PADETTO Applicant's Information APPLICANT: Lange **GROUP: 2878 Disclosure Statement** FILING DATE: December 2, 2003 (Use several sheets if necessary) **U.S. PATENT DOCUMENTS** FILING DATE IF APPROPRIATE REF. **DOCUMENT NUMBER** DATE NAME CLASS **SUB** EXAM. **CLASS INITIALS** DES. FOREIGN PATENT DOCUMENTS TRANSLATION COUNTRY CLASS **SUB** REF. **DOCUMENT NUMBER** DATE EXAM. YES/NO CLASS DES. INITIALS 00/23840 4/27/00 WO **A1** WO 02/063613 8/15/02 **A2** OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) Love et al., "Microscope Projection Photolithography for Rapid Prototyping of Masters with Micron-**A3** Scale Features for Use in Soft Lithography," Langmuir, Vol. 17, 2001, pp. 6005-6012. Genut et al., "Chemically Assisted Laser Removal of Photoresist and Particles from Semiconductor Wafers," presented at the 28th Annual Meeting of the Fine Particle Society, 1988, 11 pages.

EXAMINER: Michael Statise DATE CONSIDERED: 10-14-05

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the patent owner.